AMENDMENTS TO THE SPECIFICATION

IN THE SPECIFICATION:

Paragraph 30, page 6 has been amended as follows:

[30] Figs. 5a and 5b show TEM sectional photograph after rapid annealing for 60 second at 700 \square C 700 $^{\circ}$ C by depositing Ti thin films of 15 nm and 25 nm, respectively, on a semiconductor substrate.